

MAGPULS MP 2 BIPOLAR Pulse Power Supply









Magpuls Stromversorgungs Systeme GmbH

Im Unterfeld 19, 76547 Sinzheim, Deutschland. Germany ♥: +49 7221 987 850 | ♥: info@maqpuls.net

World Wide Sales & Support through Dynamic Partners

www.magpuls.de

Highest flexibilty

Supreme performance for Ambitious Reactive Sputtering – Production of Flat Panel Displays, Solar Cells, Decorative / Hard Coatings.

MAGPULS Bi-Polar Pulse Power Supply series MP2 are designed for operating with dual magnetrons for reactive sputtering on substrates like glass, plastic & metal & semiconductors. Individual operating modes and enhanced ARC-management allows MP2 Pulse Power Supplies to operate very effectively in achieving high quality coatings. Typical applications are production of Flat Panel Displays, Solar Cells, Decorative & Hard Coatings.

MP2 series consists of mainly two units. The first unit is the DC power supply, which provides DC power into the big capacitor bank of the pulse unit. The second unit is the Pulsar, an intelligent circuitry, which is equipped with highly sophisticated ARC

VOLTAGE PULSING - Descrete Advantage

MAGPULS MP2 Pulse Generators are designed on Voltage Pulsing Technology (VPT). Unlike in Current Pulsing Technology, users can set the amplitude of the Pulse (voltage) in VPT Pulsars. This provides a very tight control on the process. Stable plasma condition is easily achievable at low pulsing frequencies, well below 100kHz. Pulsing current is in correlation with the plasma impedance & temperature stress on the coating products can be controlled very effectively.

Features and Benefits

Adjustable Pulse Parameters & Frequency
6 Different Output operating modes
DC, Uni-Polar Pulse, Bi-Polar Pulse & Programmable Puls Train
Enhanced Effective ARC management

Independent +ve and -ve Pulse & Arc Parameters



- management capability. MP2 series units are available with an output power range from 3 kW up to 60 kW and pulse current from 35 A up to 400 A peak current.
- MP2 Duty Cycle can be adjusted individually for each half-wave to achieve higher target utilisation & for better optimisation of the processes. Enhanced ARC management provides best coating results without process interruptions. Optionally, MP2 series provides an external Optical Input Interface for external controlling of the pulse times externally. It also has as an Optical Output Interface for triggering or synchronization of other bipolar pulse power supplies of series MP1 or MP2.

>	Universal Application Range One power supply
>	Optimal adjustment of process for better process stability
	Better control of power optimized target utilization
•	Quick Arc-suppression. Lowest Arc-energy. Best results
>	Highly Effective results for Dual Sputtering processes



MP 2 BIPOLAR Pulse Power Supply

	MP2-35	MP2-100	MP2-200	MP2-400
OUT PUT				
Voltage	0 - 1000 V			
Current	0 - 5.3 A DC 0 - 35 A Pulse	0 - 38 A DC 0 - 100 A Pulse	0 - 50 A DC 0 - 200 A Pulse	0 - 120 A DC 0 - 400 A Pulse
Power	0 - 3 kW DC	0 - 15 kW DC	0 - 30 kW DC	0 - 60 kW DC
Pulse Frequency		DC or 0.05 H	lz - 100 kHz	
Max. Frequency with Max. Pulse Current	100 kHZ at 10 A 25 kHZ at 35 A	100 kHZ at 25 A 20 kHZ at 100 A	100 kHZ at 50 A 20 kHZ at 200 A	100 kHZ at 80 A 20 kHZ at 400 A
Pulse Time Settings Ton+ / Ton- / Toff+ / Toff-	2.0 μs up to 100 sec			
Duty Cycle		0.005 % t	to 100 %	
Pulse wave form	DC+, DC- Unipolar+ pulse, Unipolar- pulse Programmable Pulse Train			
IN PUT		0 100		
Max. Voltage		0 - 1000		
Max. Current	0 - 5.3 A DC			
Mains Supply	0-3 KVV DC	220 V/ AC 50/60 Hz of	- 30 KW DC	
ARC-MANAGEMENT	TΨ	230 V AC 30/60 112 01	ΓΤΦ 113 V AC 30/80	7112
Imax-Detection	0 to ±35 A peak	0 to ±100 A peak	0 to ±200 A peak	0 to ±400 A peak
ARC-Detection Time	< 200 ns			
Off Time after ARC- Detection	30 μs up to 1000 ms			
ARC-Recovery Time	≥ 100 µs			
di/dt Dynamic Change	V	/ar. di/dt threshold: 0	A/µs up to 2000 A/µs	5
Voltage Drop ΔU	Var. U threshold: 0 % up to 100 % Ubc (Option)			
U x I - Cross Detection	Var. U threshold: 0 V up to 1000 V Var. I threshold: 0.1 x max. Ipeak up to 1 x max Ipeak (Option)			
INTERFACE				
Analog	1 (up to 3) 15	pin-Sub-D for contro	olling external DC po	wer supplies
Digital	15 pin Sub-D user Interface with floating potential contactors			
RS 232	9 pin Sub-D			
Ethernet	RJ 45			
Profibus	9 pin Sub-D (Option)			
	A in an 11		· · · ·	
	Air cooling	Air cooling vvater cooling (max. water pressure 6 bar)		
Cooling Temperatur	ng lemperatur Max. 35°C 20°C - 30°C			

	MP1-35	MP	
ENV CONDITION			
Ambient Temperature			
Max. Humidity			
Max. Operation Altitude			
MECHANICAL DATA			
Construction	19"-Ra		
Dimensions H x W x D	222.25 mm x 4		
Weight	25 kg	32	
DISPLAY & CONTROLS			
Display			
LED Display			
Controls	Graphical menu via functi		
SUITABILITY			
Application	Hard Coating		
Process	PVD, Plasma Nitr Dual 8		
Material			

Please contact us for information on higher capacity models & other variants

BP Symmetric & BP Asymmetric

MP2 Pulse Generators are available in 2 variants : Bi-Polar Symmetric (MP2-S) & Bi-Polar Asymmetric (MP2-AS). In Symmetric variant, +ve and -ve Pulses will have the same Pulse Voltage settings, whereas in Asymmetric variant, users can set different values for Pulse Voltage outputs. This gives the user higher control and advantage in the Dual Magnetron Sputtering processes.

MP 2 BIPOLAR Pulse Power Supply



-100 MP1-200		MP1-400				
+ 5 °C up †	+ 5 °C up to + 35 °C					
80 % non c	80 % non condensing					
1500 m abo	ve sea level					
ack 5 HU		19"-Rack 6 HU				
83 mm x 650	0 mm	266.7 mm x 483 mm x 650 mm				
2 kg	36 kg	65 kg				
Graphic color display						
Power, OK, Start / Stop						
ion keys, arrow keys and continous rotating knob						
on Tools & Bits and BIAS application						
iding, Pulse Plasma, Reactive Sputtering, Single Magnetron Sputtering						
Metals						



OUT PUT Waveforms











Programmable Pulse Train Output				
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